AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1-19. (Canceled)

20. (New) A method of making a coated article including a coating supported by a glass substrate, the method comprising:

sputtering a first dielectric layer on the glass substrate;

sputtering a first contact layer over at least the first dielectric layer;

sputtering a target comprising Ag in an atmosphere including at least oxygen gas in order to form an infrared (IR) reflecting layer comprising AgO_x which is located over and contacts the first contact layer;

sputtering a second contact layer over and contacting the IR reflecting layer comprising AgO_x;

wherein said sputtering of at least one of the first and second contact layers comprises sputtering at least one target comprising a metal or metal alloy in an atmosphere including at least oxygen gas in order to form the contact layer(s) so as to comprise a metal oxide, and wherein more oxygen gas is introduced into said atmosphere in which the target for sputtering the contact layer(s) is located than is introduced into an

atmosphere in which the target comprising Ag used in sputtering the IR reflecting layer is located; and

wherein a ratio of (a) oxygen gas introduced into said atmosphere in which the target comprising Ag used in sputtering the IR reflecting layer is located, to (b) oxygen gas introduced into the atmosphere in which the target for sputtering the contact layer(s) is located, is from about 1:1.3 to 1:10.

21. (New) The method of claim 20, wherein the at least one of the first and second contact layers comprising the metal oxide comprises an oxide of NiCr.

22. (New) The method of claim 21, wherein each of said first and second contact layers comprises an oxide of NiCr.

23. (New) The method of claim 20, wherein the ratio is from about 1:1.5 to 1:8.

24. (New) The method of claim 20, wherein the ratio is from about 1:2 to 1:5.

25. (New) The method of claim 20, wherein from about 20-100 sccm of oxygen gas is introduced into the atmosphere in which the target comprising Ag is located.

26. (New) The method of claim 25, wherein at least one of the contact layers comprises an oxide of Ni and/or Cr.

27. (New) The method of claim 20, wherein from about 20-60 sccm of oxygen gas is introduced into the atmosphere in which the target comprising Ag is located.

28. (New) The method of claim 20, wherein both the oxygen gas and argon gas are introduced into the atmosphere in which the target comprising Ag is located, and wherein more argon gas than oxygen gas is introduced into the atmosphere in which the target comprising Ag is located.

29. (New) The method of claim 20, wherein at least one of the contact layers comprises $NiCrO_x$ and is oxidation graded so that a first portion of said one contact layer close to said infrared (IR) reflecting layer is less oxidized than a second portion of said one contact layer that is further from said infrared (IR) reflecting layer.

30. (New) The method of claim 20, further comprising heat treating the glass substrate with the coating thereon in order to thermally temper the same, and wherein visible transmission of the coated article increases as a result of said heat treating.

31. (New) The method of claim 20, wherein the first dielectric layer comprises silicon nitride.

32. (New) The method of claim 20, further comprising sputtering a layer comprising tin oxide over the second contact layer.

33. (New) The method of claim 20, further comprising sputtering a layer comprising silicon nitride over the second contact layer, and then sputtering a second IR reflecting layer comprising silver over the layer comprising silicon nitride.

34. (New) The method of claim 33, further comprising sputtering another layer comprising silicon nitride over the second IR reflecting layer comprising silver.

35. (New) The method of claim 34, wherein a layer comprising tin oxide is located over the second IR reflecting layer so as to be provided between the second IR reflecting layer and the another layer comprising silicon nitride.

36. (New) A method of making a coated article including a coating supported by a glass substrate, the method comprising:

sputtering a first dielectric layer on the glass substrate;

sputtering a first contact layer over at least the first dielectric layer;

sputtering a target comprising Ag in an atmosphere including at least oxygen gas in order to form an infrared (IR) reflecting layer comprising AgO_x which is located over and contacts the first contact layer;

sputtering a second contact layer over and contacting the IR reflecting layer comprising AgO_x;

wherein said sputtering of at least one of the first and second contact layers comprises sputtering at least one target comprising a metal or metal alloy in an atmosphere including at least oxygen gas in order to form the contact layer(s) so as to comprise a metal oxide, and

wherein more oxygen gas is introduced into said atmosphere in which the target for sputtering the contact layer(s) is located than is introduced into an atmosphere in which the target comprising Ag used in sputtering the IR reflecting layer is located.

37. (New) The method of claim 36, wherein the at least one of the first and second contact layers comprising the metal oxide comprises an oxide of NiCr.

38. (New) The method of claim 36, wherein each of said first and second contact layers comprises an oxide of NiCr.

39. (New) The method of claim 36, wherein from about 20-60 sccm of oxygen gas is introduced into the atmosphere in which the target comprising Ag is located.

40. (New) The method of claim 36, wherein both the oxygen gas and argon gas are introduced into the atmosphere in which the target comprising Ag is located, and wherein more argon gas than oxygen gas is introduced into the atmosphere in which the target comprising Ag is located.

41. (New) The method of claim 36, wherein at least one of the contact layers comprises $NiCrO_x$ and is oxidation graded so that a first portion of said one contact layer close to said infrared (IR) reflecting layer is less oxidized than a second portion of said one contact layer that is further from said infrared (IR) reflecting layer.

42. (New) The method of claim 36, wherein the first dielectric layer comprises silicon nitride.

43. (New) The method of claim 36, further comprising sputtering a layer comprising tin oxide over the second contact layer.

44. (New) The method of claim 36, further comprising sputtering a layer comprising silicon nitride over the second contact layer, and then sputtering a second IR reflecting layer comprising silver over the layer comprising silicon nitride.

45. (New) The method of claim 44, further comprising sputtering another layer comprising silicon nitride over the second IR reflecting layer comprising silver.

46. (New) The method of claim 45, wherein a layer comprising tin oxide is located over the second IR reflecting layer so as to be provided between the second IR reflecting layer and the another layer comprising silicon nitride.